Form PTO 1449 U.S. DEPARTMENT OF COMMERCE ATTY DOCKET NO. SERIAL NO. PATENT AND TRADEMARK OFFICE 210136US99 09/901,109 APPLICANT LIST OF REFERENCES CITED BY APPLICANT Ravindranath DROOPAD, et al. MAR 1 4 2003 FILING DATE **GROUP** EXAMINED FINA July 10, 2001 2815 **U.S. PATENT DOCUMENTS** DOCUMENT DATE NAME CLASS SUB FILING DATE INITIAL NUMBER **CLASS** IF APPROPRIATE 3,802,967 BWB 04/09/74 ٤ Ladany et al. AB 4,174,422 11/13/79 Matthews et al. AC 4,404,265 09/13/83 Manasevit AΠ 4,482,906 11/13/84 Hovel et al. ΑE 4,523,211 06/11/85 Morimoto et al. ΑF 4,661,176 04/28/87 Manasevit AG 4,793,872 12/27/88 Meunier et al. АН 4,846,926 07/11/89 Kay et al. A.I 4,855,249 08/08/89 Akasaki et al. 4,891,091 01/02/90 Shastry ΑK 4,912,087 03/27/90 Aslam et al. AL 4,928,154 05/22/90 Umeno et al. ΑМ 4,963,949 10/16/90 Wanlass et al. AN 5,141,894 08/25/92 Bisaro et al. ΑO 5,159,413 10/27/92 Calviello et al. 5,173,474 12/22/92 Connell et al. AQ 5,221,367 06/22/93 Chisholm et al. AR 5,225,031 07/06/93 McKee et al. AS 5,358,925 10/25/94 Neville Connell et al. ΑT 5,393,352 02/28/95 Summerfelt ΑU 5,418,216 05/23/95 Fork ΑV 5,450,812 09/19/95 McKee et al. ΑW 5,478,653 12/26/95 Guenzer AX 5,482,003 01/09/96 McKee et al. 5,514,484 05/07/96 ΑY Nashimoto ΑZ 5,556,463 09/17/96 Guenzer BA 5,588,995 12/31/96 Sheldon BB 5,670,798 09/23/97 Schetzina BC 5,733,641 03/31/98 Fork et al. BD 04/07/98 5,735,949 Mantl et al. 5,741,724 BE Ramdani et al. 04/21/98 RF 5,810,923 09/22/98 Yano et al. BG 5,830,270 11/03/98 McKee et al. ВН 5,912,068 06/15/99 Jia ΒI 6,020,222 02/01/00 Wollesen 6,045,626 04/04/00 R.I Yano et al. BK 6,064,078 05/16/00 Northrup et al. BL 6,064,092 05/16/00 Ellis-Monaghan et al. ВМ 6.096.584 08/01/00 BN 6,103,008 08/15/00 McKee et al. ВО 6,136,666 10/24/00 BP 6,174,755 01/16/01 Manning 6,180,486 01/30/01 BQ eobandung et al.

Form PTO 1449 (Modified) 2003 LIST OF REFERENCES CITED BY APPLICANT

U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE

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EXAMINER AINITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE
BWB	CA	3,766,370	10/16/73	Walther			<u> </u>
WHY	СВ	4,006,989	02/08/77	Andringa			
	СС	4,284,329	08/18/81	Smith et al.			
	CD	4,777,613	10/11/98	Shahan et al.			
	CE	4,802,182	01/31/89	Thornton et al.			
	CF	4,882,300	11/21/89	Inoue et al.			
	CG	4,896,194	01/23/90	Suzuki			
_	СН	4,999,842	03/12/91	Huang et al.			
-	СІ	5,081,062	01/14/92	Vasudev et al.			
	CJ	5,155,658	10/13/92	Inam et al.			
<u> </u>	СК	5,248,564	09/28/93	Ramesh			
_	CL	5,260,394	11/09/93	Tazaki et al.			
	СМ	5,270,298	12/14/93	Ramesh			· · · · · · · · · · · · · · · · · · ·
-	CN	5,286,985	02/15/94	Taddiken			- -
	co	5,310,707	05/10/94	Oishi et al.			
	СР	5,326,721	07/05/94	Summerfelt			
-	ca	5,404,581	04/04/95	Honjo			
_	CR	5,418,389	05/23/95	Watanabe			<u> </u>
	cs	5,436,759	07/25/95	Dijaii et al.	· .		
-	СТ	5,576,879	11/19/96	Nashimoto			<u> </u>
	cu	5,606,184	02/25/97	Abrokwah, et al.			
	cv	5,640,267	06/17/97	May et al.			
	cw	5,674,366	10/07/97	Hayashi et al.		_	
	сх	5,729,641	03/17/98	Chandonnet et al.			· · · · · · · · · · · · · · · · · · ·
	CY	5,790,583	08/04/98	Но			
	cz	5,825,799	10/20/98	Ho et al.			
	DA	5,857,049	01/05/99	Beranek et al.	-		
	DB	5,874,860	02/23/99	Brunel et al.			
	DC	5,926,496	07/20/99	Ho et al.			
	DD	5,937,285	08/10/99	Abrokwah, et al.	- 		
	DE	5,981,400	11/09/99	Lo			
	DF	5,990,495	11/23/99	Ohba		-	
	DG	6,002,375	12/14/99	Corman et al.			
	DH	6,008,762	12/28/99	Nghiem			
	DI	6,055,179	04/25/00	Koganei et al.		-	
	DJ	6,107,653	08/22/00	Fitzgerald			
	DK	6,113,690	09/05/00	Yu et al.		.	
	DL	6,114,996	09/05/00	Nghiem			
	DM	6,121,642	09/19/00	Newns			
	DN	6,128,178	10/03/00	Newns			· · · · · · · · · · · · · · · · · · ·
	DO	6,143,072	11/07/00	McKee et al.			
	DP.	6,184,144	02/06/01	Lo			
	DQ	6,222,654	04/24/01	Frigo			· · · · · · · · · · · · · · · · · · ·

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BWB	EA	4,484,332	11/20/84	Hawrylo				
1	EB	4,815,084	03/21/89	Scifres et al.				
	EC	4,876,219	10/24/89	Eshita et al.				
	ED	4,963,508	10/16/90	Umeno et al.				
	EE	5,060,031	10/22/91	Abrokwah, et al.				
1	EF	5,063,166	11/05/91	Mooney et al.				
<u> </u>	EG	5,116,461	05/26/92	Lebby et al.				
	EH	5,127,067	06/30/92	Delcoco et al.				
	ΕĪ	5,144,409	09/01/92	Ма				
	EJ	5,293,050	03/08/94	Chapple-Sokol et al			·	
	EK	5,356,831	10/18/94	Calviello et al.				
	EL	5,391,515	02/21/95	Kao et al.		1		
	ЕМ	5,442,191	08/15/95	Ма		<u> </u>		
	EN	5,444,016	08/22/95	Abrokwah, et al.		†		
	EO	5,480,829	01/02/96	Abrokwah, et al.		1		
	EP	5,528,414	06/18/96	Öakley				
	EQ	5,614,739	03/25/97	Abrokwah et al.		 		
	ER	5,729,394	03/17/98	Sevier et al.		1		
	ES	5,731,220	03/24/98	Tsu et al.				
	ET	5,764,676	06/09/98	Paoli et al.	-			
·	EU	5,777,762	07/07/98	Yamamoto				
	EV	5,778,018	07/07/98	Yoshikawa et al.				
	EW	5,778,116	07/07/98	Tomich				
	EX	5,801,105	09/01/98	Yano et al.	_	1		
	ΕΥ	5,828,080	10/27/98	Yano et al.	-			
	ΕZ	5,858,814	01/12/99	Goossen et al.				
İ	FA	5,861,966	01/19/99	Ortel				
1	FB	5,883,996	03/16/99	Knapp et al.		1 .		
	FC	5,995,359	11/30/99	Klee et al.		<u> </u>		
	FD	6,058,131	05/02/00	Pan				
	FE	6,137,603	10/24/00	Henmi				
	FF	6,146,906	11/14/00	Inoue et al.				
	FG	6,173,474	01/16/01	Conrad				
	FH	6,180,252	01/30/01	Farrell et al.				
	FI	4,242,595	12/30/0	Lehovec				
	FJ	4,398,342	08/16/83	Pitt et al.		<u> </u>		
	FK	4,424,589	01/03/84	Thomas et al.			 	
	FL	4,876,208	10/24/89	Gustafson et al.				
-	FM	4,482,422	11/84	McGinn et al.				
	FN	4,667,088	05/19/87	Kramer		1	 	
	FO	4,772,929	09/20/88	Manchester et al.				
	FP	4,841,775	06/27/89	lkeda et al.		1		
	FQ	4,845,044	07/04/89	Ariyoshi et al.	- -	1		

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U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE

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3WB	GA	4,868,376	09/19/89	Lessin et al.			
) 1 1 1 1 1 1 1 1 1 	GB	4,885,376	12/05/89	Verkade			
	GC	4,888,202	12/89	Murakami et al.			
	GD	4,891,091	12/90	Wanlass et al.	-		
	GE	5,051,790	09/24/91	Hammer			
	GF	5,055,445	10/08/91	Belt et al.	<u> </u>		
<u> </u>	GG	5,081,519	11/14/92	Nishimura et al.			
1	GН	5,143,854	09/01/92	Pirrung et al.			
	GI	5,185,589	02/09/93	Krishnaswamy et al.			
	GJ	5,191,625	03/02/93	Gustavsson			
	GК	5,194,397	03/16/93	Cook et al.			
	GL	5,208,182	05/04/93	Narayan et al.			
	GM	5,216,729	06/01/93	Berger et al.			
	GN	5,314,547	05/24/94	Heremans et al.			
	GO	5,352,926	10/04/94	Andrews			
	GP	5,356,509	10/18/94	Terranova et al.			
	GQ	5,371,734	12/06/94	Fischer			
	GR	5,372,992	12/94	Itozaki et al.			
	GS	5,405,802	04/11/95	Yamagata et al.			
	GT	5,442,561	08/15/95	Yoshizawa et al.			
	GU	5,453,727	09/26/95	Shibasaki et al.			
	GV	5,466,631	11/14/95	Ichikawa et al.			
	GW	5,473,047	12/05/95	Shi			
	GX	5,473,171	12/95	Summerfelt			
	GY	5,479,033	12/26/95	Baca et al.			
	GZ	5,486,406	01/23/96	Shi			
	HA	5,491,461	02/13/96	Partin et al.			
	нв	5,492,859	02/20/96	Sakaguchi et al.	,		
	нс	5,494,711	02/27/96	Takeda et al.			
	HD	5,504,035	04/02/96	Rostoker et al.			
	HE	5,504,183	04/02/96	Shi			
	HF	5,511,238	04/23/96	Bayraktaroglu			
	HG	5,512,773	04/96	Wolf et al.			
	нн	5,515,047	05/07/96	Yamakido et al.			
	н	5,515,810	05/14/96	Yamashita et al.			
	HJ	5,519,235	05/96	Ramesh			
	нк	5,549,977	08/96	Jin et al.			
	HL	5,551,238	09/03/96	Prueitt			
	нм	5,552,547	09/03/96	Shi			
	ΗN	5,589,284	12/31/96	Summerfelt et al.			
	но	5,602,418	02/11/97	lmai et al.			

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EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	IF APPROPRIATE	
pwb	IA	5,650,646	07/22/97	Summerfelt				
((1)	ΙB	5,656,382	08/12/97	Nashimoto				
	IC	5,659,180	08/19/97	Shen et al.				
	ID	5,661,112	08/26/97	Hatta et al.				
	ΙE	5,679,965	11/95	Schetzina				
	IF	5,725,641	03/10/98	MacLeod			,	
	iG	5,745,631	04/28/98	Reinker				
	Н	5,776,621	07/07/98	Nashimoto				
	31	5,777,350	07/07/98	Nakamura et al.				
	IJ	5,789,845	08/04/98	Wadaka et al.				
	IK	5,792,569	08/11/98	Sun et al.				
	IL.	5,792,679	08/11/98	Nakato				
-	IM	5,796,648	08/18/98	Kawakubo et al.				
	IN	5,801,072	09/01/98	Barber				
-	10	5,812,272	09/22/98	King et al.				
	IΡ	5,814,583	09/98	Itozaki et al.				
-	IQ	5,825,055	10/20/98	Summerfelt				
	IR	5,827,755	10/27/98	Yonchara et al.				
	IS	5,833,603	11/10/98	Kovacs et al.				
	ĪΤ	5,838,035	11/17/98	Ramesh				
	IU	5,844,260	12/01/98	Ohori				
	IV	5,846,846	12/08/98	Suh et al.				
	iw	5,863,326	01/26/99	Nause et al.				
	IX	5,872,493	02/16/99	Ella			_ _	
	ΙΥ	5,879,956	03/99	Seon et al.				
	IZ	5,880,452	03/09/99	Plesko				
	JA	5,883,564	03/16/99	Partin				
	JВ	5,907,792	05/25/99	Droopad et al.				
	ηC	5,937,274	08/10/99	Kondow et al.				
	ΉD	5,948,161	09/07/99	Kizuki				
	JE	5,959,879	09/28/99	Коо			·	
	IJF	5,966,323	10/99	Chen et al.			•	
	μG	5,987,011	11/16/99	Toh				
	μн	6,022,140	02/08/00	Fraden et al.		$oxed{oxed}$		
	λı	6,022,410	02/08/00	Yu et al.				
	ηJ	6,023,082	02/08/00	McKee et al.				
	JК	6,028,853	02/22/00	Haartsen				
	JL	6,049,702	04/11/00	Tham et al.				
	ЛW	6,078,717	06/20/00	Nashimoto et al				
	JИ	6,088,216	07/00	Laibowitz et al.				
	hΟ	6,090,659	07/00	Laibowitz et al.				
	JP	6,107,721	08/22/00	Lakin				
	hα	6,153,010	11/28/00	Kiyoku et al				

ERENCES CITED BY APPLICANT

U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE

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E	XAMINER		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE	
	B Wb	KA	6,153,454	11/28/00	Krivokapic		CLASS	II AFFROMIATE	
H	1 8 / / / / 	КВ	6,191,011	02/01	Gilboa et al				
	+	кс	6,204,737	03/20/01	Ella				
\vdash		KD	6,224,669	05/01/01	Yi et al.				
		KE	6,225,051	05/01/01	Sugiyama et al.				
	<u> </u>	KF	6,241,821	06/05/01	Yu et al.				
\vdash		KG	6,265,749	07/24/01	Gardner et al.		i		
r		кн	6,313,486	11/01	Kencke et al.		h · · 		
r		KI	6,316,832	11/13/01	Tsuzuki et al.				
		KJ	2002/0008234	01/02	Emrick				
╟		кк	3,670,213	06/13/72	Nakawaga et al.				
r		KL	4,756,007	07/05/88	Qureshi et al.			,	
		км	4,773,063	09/20/88	Hunsperger et al.				
		KN	5,394,489	02/28/95	Koch				
		ко	5,406,202	04/11/95	Mehrgardt et al.				
Г		KP	5,528,067	06/18/96	Farb et al.				
r		ΚQ	5,572,052	11/05/96	Kashihara et al.			-	
		KR	5,767,543	06/16/98	Ooms et al.				
		ĸs	6,175,497	01/16/01	Tseng et al.				
Г		кт	6,197,503	03/06/01	Vo-Dinh et al.				
Г		ΚU	6,248,459	06/19/01	Wang et al.				
		ΚV	6,252,261	06/26/01	Usui et al.				
		kw	6,255,198	07/03/01	Linthicum et al.				
		кх	6,268,269	07/31/01	Lee et al.				
Г		KY	6,291,319	09/18/01	Yu et al.				
		ΚZ	6,316,785	11/13/01	Nunoue et al.				
		LA	6,343,171	01/29/02	Yoshimura et al.				
		LB	4,965,649	10/23/90	Zanio et al.				
		LC	6,253,649	05/01	Kawahara et al.				
		LD	6,211,096	04/01	Allman et al.			<u> </u>	
Ĺ		LE	6,239,449	05/29/01	Fafard et al.				
L		LF	2001/0013313	08/16/01	Droopad et al.		<u> </u>	·	
Ĺ		LG	6,184,044	02/06/01	Sone et al.				
Ĺ		L	6,011,646	01/04/00	Mirkarimi et al.				
L		LI	5,227,196	07/13/93	Itoh				
		LJ	6,150,239	11/21/00	Goesele et al.				
		LK	5,441,577	08/15/95	Sasaki et al.			····	
L		LL	4,459,325	07/10/84	Nozawa et al.			· · · · · · · · · · · · · · · · · · ·	
L		LM	4,392,297	07/12/83	Little				
<u> </u>	\Box	LN	4,289,920	09/15/81	Hovel				
L		LO	5,281,834	01/25/94	Cambou et al.				
		LP	4,901,133	02/13/90	Curran et al.				
		LQ	5,514,904	05/07/96	Onga et al.				

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				U.S. PATENT DOCUMENTS			
EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE
BNB	MA	5,553,089	09/03/96	Seki et al.			
	МВ	5,528,057	06/18/96	Yanagase et al.			
	МС	6,229,159	05/08/01	Suzuki			
	MD	4,748,485	05/31/88	Vasudev			
	ME	4,984,043	01/08/91	Vinal			
	MF	5,754,319	05/19/98	Van De Voorde et al.			
	MG	6,108,125	08/22/00	Yano			
	МН	5,073,981	12/17/91	Giles et al.			
	МІ	5,140,651	08/18/92	Soref et al.			·
	MJ	5,610,744	03/11/97	Ho et al.			
	MK	6,362,017	03/26/02	Manabe et al.			-
	ML	6,242,686	06/05/01	Kishimoto et al.			
	ММ	5,689,123	11/18/97	Major et al.			
	MN	5,670,800	09/23/97	Nakao et al.			
	МО	5,067,809	11/26/91	Tsubota			
	MP	5,596,205	01/21/97	Reedy et al.			
	MQ	6,175,555	01/16/01	Hoole			
	MR	5 ,357,122	10/18/94	Okubora et al.			
	MS	4,084,130	04/11/78	Holton			
	MT	6,093,302	07/25/00	Montgomery			
	MU	6,372,813	04/16/02	Johnson et al.			
	MV	5,608,046	03/04/97	Cook et al.			
	MW	5,955,591	09/21/99	Imbach et al.			
	MX	6,022,963	02/08/00	McGall et al.			-
	MY	6,083,697	07/04/00	Beecher et al.			
	MZ	5,063,081	11/05/91	Cozzette et al.			
	NA	5,479,317	12/26/95	Ramesh			
	NB	5,306,649	04/26/94	Hebert		·	
	NC	5,962,069	10/05/99	Schindler et al.			
	ND	5,541,422	07/30/96	Wolf et al.			
	NE	5,873,977	02/23/99	Desu et al.			
	NF	5,538,941	07/23/96	Findikoglu et al.			
	NG	6,046,464	04/04/00	Schetzina			
	NH	6,235,145	05/22/01	Li et al.			
	NI	5,610,744	03/11/97	Ho et al.			
	NJ	5,280,013	01/18/94	Newman et al.			
	NK	6,348,373 B1	02/19/02	Ma et al.			
	NL	6,339,664 B1	01/15/02	Farjady et al.	·		
	NM	4,439,014	03/27/84	Stacy et al.		-	
	NN	4,889,402	12/26/89	Reinhart			
	NO	5,963,291	10/05/99	Wu et al.	-		
	NP	6,011,641	01/04/00	Shin et al.			
	NQ	6,340,788 B1	01/22/02	King et al.			· · ·

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U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE

ATTY DOCKET NO. 210136US99 SERIAL NO.

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LIST OF FERENCES CITED BY APPLICANT

Ravindranath DROOPAD, et al.

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U.S. PA	TENT	DOCU	JMENTS
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EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE
BINB	OA	5,807,440	09/15/98	Kubota et al.			
1	ОВ	4,681,982	07/21/87	Yoshida			
	ос	4,629,821	12/16/86	Bronstein-Bonte et al.			
	OD	4,452,720	06/05/84	Harada et al.			
	OE	3,935,031	01/27/76	Adler			
	OF	5,760,426	06/02/98	Marx et al.			
	OG	5,053,835	10/01/91	Horikawa et al.			
	ОН	6,326,645 B1	12/04/01	Kadota			
	OI	5,770,887	06/23/98	Tadatomo et al.			
	ΟĴ	6,372,356 B1	04/16/02	Thornton et al.			
	ок	4,774,205	09/27/88	Choi et al.			
	OL	6,359,330 B1	03/19/02	Goudard			
	ОМ	5,312,765	05/17/94	Kanber			
	ON	5,734,672	03/31/98	McMinn et al.			
	00	6,367,699 B2	04/09/02	Ackley			
	OP	5,530,235	06/25/96	Stefik et al.			
	OQ	5,623,552	04/22/97	Lane			
	OR	5,481,102	01/02/96	Hazelrigg, Jr.		-	
	os	6,134,114	10/17/00	Ungermann et al.			
	ОТ	5,984,190	11/16/99	Nevill			
	ΟU	5,789,733	08/04/98	Jachimowicz et al.			
	ov	5,753,300	05/19/98	Wessels et al.			-
	ow	6,208,453	03/27/01	Wessels et al.			
	ох	5,886,867	03/23/99	Chivukula et al.			· · · · · · · · · · · · · · · · · · ·
	OY	5,028,976	07/02/91	Ozaki et al.			-
	ΟZ	5,869,845	02/09/99	Vander Wagt et al.			
	PA	5,596,214	01/21/97	Endo			
	РВ	6,391,674 B2	05/21/02	Ziegler	·		
	PC	6,275,122 B1	08/14/01	Speidell et al.			
	PD	6,238,946 B1	05/29/01	Ziegler			
	PE	6,210,988 B1	04/03/01	Howe et al.			
	PF	6,392,257	05/21/02	Ramdani et al.			
	PG	4,442,590	04/17/84	Stockton et al.			
	PH	5,603,764	02/18/97	Matsuda et al.			<u> </u>
	PI	6,087,681	06/11/00	Shakuda			
	PJ	5,132,648	07/21/92	Trinh et al.			
	PK	6,427,066	07/30/02	Grube			
	PL	2002/0072245	06/13/02	Ooms et al.	-		
	РМ	6,278,138 B1	08/21/01	Suzuki			
	PN	5,888,296	03/30/99	Ooms et al.			
	PO	5,198,269	03/3093	Swartz et al.		1	
	PP	2002/0030246	03/14/02	Eisenbeiser et al.			
	PQ	2002/0047143	04/25/02	Ramdani et al.	1		

Form PTO 1449 (Modified) AAR 1 4 2003 LID ERENCES CITED BY APPLICANT

U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE

ATTY DOCKET NO. 210136US99 SERIAL NO.

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Ravindranath DROOPAD, et al. GROUP

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U.S. PATENT DOCUMENTS

XAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE
3WB	QA	5,776,359	07/07/98	Schultz et al.			
J * V - Y	QB	5,569,953	10/29/96	Kikkawa et al.			
	QC	5,834,362	11/10/98	Miyagaki et al.			
	QD	6,248,621 B1	06/19/01	Wilk et al.			
	QE	5,266,355	11/30/93	Wernberg et al.			
	QF	6,277,436 B1	08/21/01	Stauf et al.			
	QG	6,039,803	03/21/00	Fitzgerald et al.			
	QH	5,619,051	04/08/97	Endo			
	QI	5,420,102	05/30/95	Harshavardhan et al.			
	QJ	5,210,763	05/11/93	Lewis et al.			
	QK	5,103,494	04/07/92	Mozer			
	QL	4,594,000	06/10/86	Falk et al.			
	QM	4,297,656	10/27/81	Pan			
	QN	5,244,818	09/14/93	Jokers et al.			
	QO	6,048,751	04/11/00	D'Asaro et al.			
	QP	5,484,664	01/16/96	Kitahara et al.			
	QQ	5,780,311	07/14/98	Beasom et al.			
	QR	6,438,281 B1	08/20/02	Tsukamoto et al.			
	QS	5,399,898	03/21/95	Rostoker			
	QT	6,271,619	08/07/01	Yamada et al.			
	QU	5,334,556	08/02/94	Guldi			
	QV	4,910,164	03/20/90	Shichijo			
	QW	4,952,420	08/28/90	Walters			
	QX	6,121,647	09/19/00	Yano et al.			
	QΥ	6,306,668 B1	10/23/01	McKee et al.			
	QZ	6,143,366	11/07/00	Lu			
	RA	6,410,941	06/25/02	Taylor et al.			
	RB	5,397,428	03/14/95	Stoner et al.			
	RC	6,432,546 B1	08/13/02	Ramesh et al.			
	RD	6,345,424	02/12/02	Hasegawa et al.			
	RE	6,338,756 B2	01/15/02	Dietze			
	RF	5,516,725	05/14/96	Chang et al.			
	RG	4,667,212	05/19/87	Nakamura			
	RH	5,629,534	05/13/97	Inuzuka et al.			
	RI	3,914,137	10/21/75	Huffman et al.			
	RJ	5,753,928	05/19/98	Krause			
	RK	5,977,567	11/02/99	Verdiell			
	RL	5,130,762	07/14/92	Kulick			
	RM	5,621,227	04/15/97	Joshi			
	RN	6,389,209 B1	05/14/02	Suhir			
	RO	5,163,118	11/10/92	Lorenzo et al.			
	RP	5,926,493	07/20/99	O'Brien et al.			
] [RQ	5,323,023	06/21/94	Fork			

Form PTO 1449 (Modified) MAR 1 4 2003 LIST OF RE RENCES CITED BY APPLICANT

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U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE

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U.S.	PAT	ENT	DOC	JMENTS
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(AMINER		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE
5WB	SA	6,156,581	12/05/00	Vaudo et al.			
1	SB	5,395,663	03/07/95	Tabata et al.			
	SC	4,146,297	03/27/79	Alferness et al.			
	SD	5,452,118	09/19/95	Maruska			
	SE	5,889,296	03/30/99	Imamura et al.			
	SF	6,300,615 B1	10/09/01	Shinohara et al.			
	SG	6,232,910 B1	05/15/01	Bell et al.			
	SH	5,686,741	11/11/97	Ohori et al.			
	SI	4,959,702	09/25/90	Moyer et al			
	SJ	6,100,578	08/08/00	Suzuki			
	SK	6,410,947 B1	06/25/02	Wada			
1	SL	6,417,059 B2	07/09/02	Huang			
	SM	6,461,927 B1	10/08/02	Mochizuki et al.			
	SN	6,462,360 B1	10/08/02	Higgins, Jr. et al.			
	so	5,981,976	11/09/99	Murasato			
	SP	5,981,980	11/09/99	Miyajima et al.	1		
	SQ	2002/0006245 A1	01/17/02	Kubota et al.			
	SR	2002/0131675 A1	09/19/02	Litvin			
	SS	6,256,426 B1	07/03/01	Duchet	1		
	ST	6,278,523 B1	08/21/01	Gorecki			-
	SU	6,319,730 B1	11/20/01	Ramdani et al.			
	sv	6,404,027	06/11/02	Hong et al.			
	sw	6,312,819 B1	11/06/01	Jia et al.			
	SX	5,119,448	06/02/92	Schaefer et al.			-
1 1	SY	4,120,588	10/17/78	Chaum		•	
	SZ	5,194,917	03/16/93	Regener			
	TA	5,018,816	05/28/91	Murray et al.			
	ТВ	5,953,468	09/14/99	Finnila et al.			· · · · · · · · · · · · · · · · · · ·
	тс	5,561,305	10/01/96	Smith	-		
_	TD	5,896,476	04/20/99	Wisseman et al.			
1	TE	4,934,777	06/19/90	Jou et al.			-
-	TF	6,320,238 B1	11/20/01	Kizilyalli et al.			
	TG	6,393,167 B1	05/21/02	Davis et al.			
	TH	5,760,427	06/02/98	Onda			
1	TI	6,411,756 B2	06/25/02	Sadot et al.			
	TJ	5,668,048	09/16/97	Kondo et al.			
1	TK	5,852,687	12/22/98	Wickham			
1	TL	5,122,852	06/16/92	Chan et al.			
T	TM	5,173,835	12/22/92	Cornett et al.			
	TN	5,055,835	10/08/91	Sutton			
	то	6,139,483	10/31/00	Seabaugh et al.			
1 1	TP	5,283,462	02/01/94	Stengel			
1	TQ	6,103,403	08/15/00	Grigorian et al.			

U.S. DEPARTMENT OF COMMERCE ATTY DOCKET NO. SERIAL NO. (Modified) 210136US99 09/901,109 4 2003 **APPLICANT** MEST OF REFERENCES CITED BY APPLICANT Ravindranath DROOPAD, et al. **FILING DATE GROUP** July 10, 2001 2815 **U.S. PATENT DOCUMENTS DOCUMENT EXAMINER** SUB **FILING DATE** DATE **CLASS** NAME NUMBER **CLASS** IF APPROPRIATE INITIAL UA 06/03/97 5,635,433 Sengupta UΒ 5,427,988 06/27/95 Sengupta et al. UC 6,297,842 B1 10/02/01 Koizumi et al. UD 10/28/97 Takahashi et al. 5,682,046 01/19/93 ŲΕ 5,181,085 Moon et al. UF 6,051,858 04/18/00 Uchida et al. 01/11/00 Wallace et al. UG 6,013,553 10/03/89 UH 4,872,046 Morkoc et al. UI 2002/0047123 A1 04/25/02 Ramdani et al. UJ 5,995,528 11/30/99 Fukunaga et al. UK 5,075,743 12/24/91 Behfar-Rad UL 08/01/95 Paoli et al. 5,438,584 UM 4,503,540 03/05/85 Nakashima et al. UN 5,373,166 12/13/94 Buchan et al. UO 6,278,137 B1 08/21/01 Shimoyama et al. 5,623,439 04/22/97 UP Gotoh et al. UQ 01/01/91 Ohno et al. 4,981,714 UR 6,194,753 B1 02/27/01 Seon et al. 6,326,637 B1 12/04/01 US Parkin et al. UT UÜ UV UW UX UY UΖ VA VΒ VC VD VΕ VF VG VΗ VΙ VJ VΚ ۷Ļ VΜ VN VO VΡ

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Form PTO 1449 (Modified) MAR 1 4 2003 LIST OF REFERENCES CITED BY APPLICANT

U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE

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Ravindranath DROOPAD, et al. **GROUP**

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/ //	AAA	0 250 171	12/23/87	EP	YES X	. NO		
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	AAK	11-238683	08/31/99	Japan	×			
	AAL	11-260835	09/24/99	Japan w/English Abstract	×			
	AAM	HEI 2-391	01/05/90	Japan w/English Abstract	×			
1	AAN	5-48072	02/26/93	Japan w/English Abstract	×			
 	AAO	52-88354	07/23/77	Japan w/English Abstract	×			
1	AAP	54-134554	10/19/79	Japan w/English Abstract	×			
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1	AAS	6-232126	08/19/94	Japan	×			
 	AAT	6-291299	10/18/94	Japan w/English Abstract	×			
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 	AAW	63-198365	08/17/88	Japan w/English Abstract	×			
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 		WO 00/48239	08/17/00	WIPO				
1		WO 99/14797	03/25/99	WIPO				
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U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE

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		NUMBER			YES N	0
1WB	BAA	1 043 426	10/11/00	Europe		
	BAB	2000-068466	03/00	Japan (Abstract)		
	BAC	64-50575	02/27/89	Japan		
	BAD	WO 98/05807	01/12/98	WIPO		
1	BAE	WO 94/03908	02/17/94	WIPO		
	BAF	WO 01/33585	05/10/01	WIPO		
	BAG	1-102435	04/20/89	Japan w/English Abstract		
	ВАН	52-135684	11/12/77	Japan (English Abstract)		
	BAI	02051220	02/21/90	Japan (English Abstract)		
	BAJ	11135614	05/21/99	Japan (w/English Abstract)		
	BAK	64-52329	02/28/89	Japan (w/English Abstract)		
	BAL	10-256154	09/25/98	Japan (w/English Abstract)		
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	BAN	10-303396	11/13/98	Japan (w/English Abstract)		
	ВАО	58-213412	12/12/83	Japan w/English Abstract		·
1	BAP	0 964 259	12/15/99	Europe		
	BAQ	0 875 922	11/04/98	Europe		
	BAR	61-63015	04/01/86	Japan w/English Abstract		
	BAS	11340542	12/10/99	Japan (English Abstract)		
	BAT	WO 01/37330	05/25/01	WIPO		
1	BAU	0 331 467	09/06/89	Europe	-	
	BAV	WO 00/16378	03/23/00	WIPO		
	BAW	0 926 739	06/30/99	Europe		
	BAX	0 964 453	12/15/99	Europe		
	BAY	5-152529	06/18/93	Japan w/English Abstract	·	
	BAZ	9-67193	03/11/97	Japan w/English Abstract		
1	BBA	9-82913	03/28/97	Japan w/English Abstract		
	BBB	0 309 270	03/29/89	Europe		
- t	ввс	EP 0 957 522	11/17/99	Europe		
<u> </u>	BBD	EP 0 810 666	12/03/97	Europe		
- 	BBE	1-179411	07/17/89	Japan w/English Abstract		
	BBF	DE 100 17 137	10/26/00	GERMANY		
+	BBG	WO 02 01648	01/03/02	WIPO		
	ввн	WO 02/33385 A2	04/25/02	WIPO		
	ВВІ	WO 01/59814 A2	08/16/01	WIPO		
1	ВВЈ	WO 02/09160 A2	01/31/02	WIPO		
	ввк	WO 00/06812	02/10/00	WIPO		
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ATTY DOCKET NO. SERIAL NO. U.S. DEPARTMENT OF COMMERCE Form PTO 1449 PATENT AND TRADEMARK OFFICE (Modified) 210136US99 09/901,109 AR 1 4 2063 **APPLICANT** LIST OF REFERENCES CITED BY APPLICANT Ravindranath DROOPAD, et al. GROUP FILING DATE PADEMA July 10, 2001 2815 FOREIGN PATENT DOCUMENTS DOCUMENT COUNTRY TRANSLATION DATE NUMBER YES NO 52-89070 07/26/77 xx BWB Japan CAA 01/17/01 Europe CAB EP 1 069 606 CAC WO 02/03113 01/10/02 WIPO 01/10/02 WIPO CAD WO 02/03467 EUROPE 12/21/94 0 630 057 CAE CAF 61-36981 02/21/86 Japan w/English Abstract CAG WO 93/07647 04/15/93 WIPO 01/11/02 Japan w/English Abstract CAH 2002-9366 EP 0 881 669 12/02/98 CAI Europe WIPO CAJ WO 02/03480 01/10/02 06/27/02 WIPO CAK WO 02/50879 CAL EP 0 777 379 06/04/97 Europe CAM WO 01/04943 A1 WIPO XX 01/18/01 WIPO WO 02/47127 A2 06/13/02 CAN Japan w/English Abstract CAO JP 58-075868 05/07/83 CAP EP 0 993 027 04/12/00 Europe EP 0 711 853 05/15/96 Europe CAQ WO 98/20606 WIPO CAR 05/14/98 10/11/00 CAS EP 1 043 765 Europe CAT 0 300 499 01/25/89 Europe EP 1 085 319 03/21/01 Europe CAU CAV WO 01/16395 03/08/01 WIPO CAW 2000-351692 12/19/00 Japan w/English Abstract 08/16/91 Japan (English Abstract only) CAX 03-188619 CAY 63-289812 11/28/88 Japan (English Abstract only) CAZ EP 0 884 767 12/16/98 Europe 03/11/94 Japan (English Abstract only) 06-069490 CBA CBB WO 01/59821 A1 08/16/01 WIPO CBC CBQ CBE CBF CBG СВН СВІ CBJ СВК CBL СВМ CBN СВО CBP

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SHEET 15 OF 23 ATTY DOCKET NO. SERIAL NO. Form PTO 1449 U.S. DEPARTMENT OF COMMERCE MAR 1 4 2013 TENT AND TRADEMARK OFFICE 210136US99 09/901.109 **APPLICANT** LIST OF REFERENCES CITED BY APPLICANT Ravindranath DROOPAD, et al. **FILING DATE GROUP** July 10, 2001 2815 OTHER REFERENCES (Including Author, Title, Date, Pertinent Pages, etc.) Nakagawara et al., "Effects of Buffer Layers in Epitaxial Growth of SrTiO₃ Thin Film on Si(100), J. Appl. Phys., 78 (12), December 15, 1995, pp. 7226-7230. Suzuki et al., "A Proposal of Epitaxial Oxide Thin Film Structures For Future Oxide Electronics," Materials Science and CCAB Engineering B41, (1996), pp. 166-173. W. F. Egelhoff et al., "Optimizing GMR Spin Valves: The Outlook for Improved Properties", 1998 Int'l Non Volatile Memory CCAC Technology Conference, pp. 34-37. CCAD Wang et al., "Processing and Performance of Piezoelectric Films", Univ. Of MD, Wilcoxon Research Col, and Motorola Labs, May 11, 2000. CCAE M. Rotter et al., "Nonlinear Acoustoelectric Interactions in GaAs/LiNbO₃ Structures", Applied Physics Letters, Vol. 75(7), August 16, 1999, pp. 965-967. K. Sreenivas et al., "Surface Acoustic Wave Propagation on Lead Zirconate Titanate Thin Films," Appl. Phys. Lett. 52 (9), Feb. 29, 1998, pp. 709-711. CCAF M. Rotter et al., "Single Chip Fused Hybrids for Acousto-Electric and Acousto-Optic Applications," 1997 Applied Physics CCAG Letters, Vol. 70(16), April 21, 1997, pp. 2097-2099. A. Mansingh et al., "Surface Acoustic Wave Propagation in PZT/YBCO/SrTiO₃ and PbTiO₃/YBCO/SrTiO₃ Epitaxial CCAH Heterostructures," Ferroelectric, Vol. 224, pages 275-282, 1999. CCAI S. Mathews et al., "Ferroelectric Field Effect Transistor Based on Epitaxial Perovskite Heterostructures", Science, Vol. 276, April 11, 1997, pp. 238-240. CCAJ R. Houdre et al., "Properties of GaAs on Si Grown by Molecular Beam Epitaxy," Solid State and Materials Sciences, Vol. 16, Issue 2, 1990, pp. 91-114. CCAK S. F. Fang et al., "Gallium Arsenide and Other Compound Semiconductors on Silicon," J. Appl. Phys., 68(7), October 1, 1990, pp. R31-R58. CCAL Carlin et al., "Impact of GaAs Buffer Thickness on Electronic Quality of GaAs Grown on Graded Ge/GeSi/Si Substrates, Appl. Phys. Letter, Vol. 76, No. 14, April 2000, pp. 1884-1886. CCAM Ringel et al., "Epitaxial Integration of III-V Materials and Devices with Si Using Graded GeSi Buffers," 27th International Symposium on Compound Semiconductors, Oct. 2000. CCAN Zogg et al., "Progress in Compound-Semiconductor-on-Silicon-Heteroepitaxy with Fluoride Buffer Layers," J. Electrochem Soc., Vol. 136, No. 3, March 1998, pp. 775-779. Xiong et al., "Oxide Defined GaAs Vertical-Cavity Surface-Emitting Lasers on Si Substrates," IEEE Photonics Technology CCAO Letters, Vol. 12, No. 2, Feb. 2000, pp. 110-112. CCAP Clem et al., "Investigation of PZT//LSCO//Pt//Aerogel Thin Film Composites for Uncooled Pyroelectric IR Detectors," Mat. Res. Soc. Symp. Proc., Vol. 541, pp. 661-666, 1999.

*Examiner: Initial if reference is considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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September 1998.

Gunapala et al., "Bound-To-Quasi-Bound Quantum-Well Infrared Photodetectors," NASA Tech Brief, Vol. 22, No. 9,

Date Considered

Examiner Date Considered

*Examiner: Initial if reference is considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

Electronics, 2000, Book of Abstracts, IWCE Glasgow 2000, 7th Int'l Workshop on, 2000; pp. 64-65

DDAQ Kihong KIM, et al." On-Chip Wireless Interconnection with Integrated Antennas"; 2000 IEEE; pp. 20.2.1-20.3.4

DDAP S.S. LU, et al.; "Piezoelectric field effect transistor (PEFET) using In_{0.2}Ga_{0.8}As/Al_{0.35}Ga_{0.65}As/In_{0.2}Ga_{0.8}As/GaAs Strained layer structure on (111)B GaAs substrate"; ELECTRONICS LETTERS, 12TH Ma 1994, Vol. 30, No. 10; pp. 823-825

U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE ATTY DOCKET NO. SERIAL NO. (Modified) AR 1 4 2003 210136US99 09/901,109 **APPLICANT** FERENCES CITED BY APPLICANT Ravindranath DROOPAD, et al. FILING DATE **GROUP** MADEMA July 10, 2001 2815 OTHER REFERENCES (Including Author, Title, Date, Pertinent Pages, etc.)
EEAA G. PASSIOPOULOS, et al.; "V-BAND SINGLE CHIP, DIRECT CARRIER BPSK MODULATION TRANSMITTER WITH INTEGRATED PATCH ANTENNA"; 1998 IEEE MTT-S DIGEST; pp. 305-308 EEAB Mau-Chung Frank CHANG, et al.; "RF/Wireless Interconnect for Inter- and Intra-Chip Communications"; Proceedings of the IEEE, Vol. 89, No. 4, April 2001; pp. 456-466 EEAC The Electronics Industry Report; Prismark; 2001; pp. 111-120 EEAD J.K. ABROKWAH, et al.; "A Manufacturable Complementary GaAs Process"; GaAs IC Symposium, IEEE, 1993; pp. 127-130 EEAE H. Nagata, "A Preliminary Consideration of the Growth Behaviour of CeO2, SrTiO3 and SrVO3 Films on Si Substrate," Thin Solid Films, 224, 1993, pp. 1-3. Nagata et al., "Heteroepitaxial Growth of CeO₂(001) Films on Si(001) Substrates by Pulsed Laser Deposition in Ultrahigh EEAF Vacuum," Jpn. Jour. Appl. Phys., Vol. 30, No. 6B, June 1991, pp. L1136-L1138. EEAG Kado et al., "Heteroepitaxial Growth of SrO Films on Si Substrates," J. Appl. Phys., 61(6), March 15, 1987, pp. 2398-2400. EEAH H. Ishiwara et al., "Epitaxial Growth of Perovskite Type Oxide Films on Substrates"; Materials Research Symposium Proceedings, Vol. 220, pp. 595-600, April 29 - May 3, 1991. EEAI J.K. Abrokwah, et al.; "A Manufacturable High-Speed Low-Power Complementary GaAs Process"; Extended Abstracts of the 1994 International Conference on Solid State Devices and Materials, Yokohama, 1994, pp.592-594 EEAJ C.J. Palmstrom et al.; "Stable and Epitaxial Contacts to III-V Compound Semiconductors"; Contacts to Semiconductors Fundamentals and Technology, Novles Publications, 1993; pp.67-150 EEAK Jayshri SABARINATHAT, et al.; "Submicron three-dimensional infrared GaAs/Al_xO_y-based photonic crystal using single-step

Date Considered Examiner: Initial if reference is considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

epitaxial growth"; APPLIED PHYSICS LETTERS, VOLUME 78, NUMBER 20, 14 MAY 2001; pp.3024-3026

EEAM John D. JOANNOPOULOS, et al.; "Molding the Flow of Light"; Photonic Crystals; Princeton University Press, 1995

EEAN Thomas F. KRAUSS, et al.; "Photonic crystals in the optical regime - past, present and future"; Progress in Quantum

EEAO G. H. JIN, et al.; "PLZT Film Waveguide Mach-Zehnder Electrooptic Modulator"; Journal of Lightwave Technology, Vol. 18,

D.E. ASPNES, et al.; "Steps on (001) silicon surfaces"; J. Vac. Sci. Technol. B, Vol. 5, No. 4, Jul/Aug 1987; pp. 939-944 EEAQ D.M. NEWNS, et al.; "Mott transition field effect transistor"; APPLIED PHYSICS LETTERS, VOLUME 73, NUMBER 6, 10

EEAL Philip BALL; "The Next Generation of Optical Fibers"; Technology Review, May 2001; pp.55-61

Electronics 23 (1999) 51-96

No. 6. June 2000; pp.807-812

AUGUST 1998; pp.780-782

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SHEET 18 OF 23 Form PTO 1449 U.S. DEPARTMENT OF COMMERCE ATTY DOCKET NO. SERIAL NO. (Modified) ATENT AND TRADEMARK OFFICE MAR 1 4 2003 09/901,109 210136US99 APPLICANT Ravindranath DROOPAD, et al. ERENCES CITED BY APPLICANT FILING DATE GROUP DADEMA July 10, 2001 2815 OTHER REFERENCES (Including Author, Title, Date, Pertinent Pages, etc.) FFAA Lucent Technologies, Inc. "Arrayed Waveguide Grating Multiplexer/Demultiplexer"; January 2000; 4 pages Hisashi SHICHIJO, et al.; "Co-Integration of GaAs MESFET and Si CMOS Circuits"; IEEE ELECTRON DEVICE LETTERS, FFAB VOL. 9, NO. 9, SEPTEMBER 1988; pp.444-446 FFAC H. SHICHIJO, et al.; "GaAs MESFET and Si CMOS Cointegration and Circuit Techniques"; 1988 IEEE; GaAs IC Symposium FFAD H. SHICHIJO, et al.; "Monolithic Process for Co-Integration of GaAs and Silicon Circuits"; 1988 IEEE; pp.778-781 FFAE Z.H. ZHU, et al. "Growth of InGaAs multi-quantum wells at 1.3 m wavelength on GaAs compliant substrates"; APPLIED PHYSICS LETTERS, VOLUME 72, NUMBER 20, 18 MAY 1998; pp.2598-2600 FFAF Kurt EISENBEISER, et al.; "Metamorphic InAlAs/InGaAs Enhancement Mode HEMT's on GaAs Substrates"; IEEE ELECTRON DEVICE LETTERS, VOL. 20, NO. 10, OCTOBER 1999; pp.507-509 FFAG Tomonori NAGASHIMA, et al.; "Three-Terminal Tandem Solar Cells With a Back-Contact Type Bottom Cell" Higashifuji Fechnical Center, Toyota Motor Corporation; 4 pages FFAH James SCHELLENBERG, et al.; "Low-Loss, Planar Monolithic Baluns for K/Ka-Band Applications"; 1999 IEEE MTT-S Digest; pp.1733-1736 Arnold Leitner et al; "Pulsed Laser Deposition of Superconducting Strontium Titanate Thin-Films"; ; Session K11-Thin Films and Borocarbides; Mixed Session, Wednesday Afternoon; March 19 1997; Room 1202 B, Conv. Center (Abstract) R.D. VISPUTE; "High quality optoelectronic grade epitaxial AIN films on -Al₂0₃, Si and 6H-SiC by pulsed laser deposition"; Thin Solid Films 299 (1997), pp.94-103 FFAK T. Warren WEEKS, et al.; "GaN thin films deposited via organometallic vapor phase epitaxy on (6H)-SiC(0001) using hightemperature monocrystalline AIN buffer layers" 320 Applied Physics Letters, Vol. 67, No. 3, 17 July 1995, ppl401-403 FFAL Z. YU, et al.; "Epitaxial oxide thin films on SI(001)*"; J. Vac. Sci. Technol. B. Vol. 18, No. 4, Jul/Aug 2000; pp.2139-2145 FFAM Gentex Corporate Website; "Photoelectric Smoke Detectors - How They Work; 2001 FFAN Jeffrey B. Casady, et al.; "A Hybrid 6H-SiC Temperature Sensor Operational from 25 C to 500 C"; IEEE TRANSACTIONS ON COMPONENTS, PACKAGING, AND MANUFACTURING TECHNOLOGY - PART A, VOL. 19, NO. 3, SEPTEMBER 1996; pp. 416-422

*Examiner: Initial if reference is considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

FFAQ D.A. FRANCIS, et al.; "A single-chip linear optical amplifier"; OFC, 2001; March 17-22, 2001

Hill, Inc., 1994; Chapter Twenty Seven

March 2001; pp. 37-42

FFAO Ronald W. WAYNANT, et al.; "OPTOELECTRONIC INTEGRATED CIRCUITS"; ELECTRO-OPTICS HANDBOOK, McGraw-

FFAP Antonio MECOZZI, et al.; "The Roles of Semiconductor Optical Amplifiers in Optical Networks"; Optics & Photonics News;

Date Considered

09/901,109

Form PTO 1449 (Modified) AR 1 2003

U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE

ERENCES CITED BY APPLICANT

ATTY DOCKET NO. 210136US99 SERIAL NO.

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Ravindranath DROOPAD, et al.

FILING DATE

GROUP

July 10, 2001

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COADED		July 10, 2001 2013
		OTHER REFERENCES (Including Author, Title, Date, Pertinent Pages, etc.)
BNB	GGAA	G. Vogg et al.; "Epitaxial alloy films of zintl-phase Ca(Si1-xGex)2"; Journal of Crystal Growth 223 (2001); pp. 573-576
1	GGAB	Peter S. GUILFOYLE, et al.; "Optoelectronic Architecture for High-Speed Switching and Processing Applications"; 1998 Th Photonics Design and Applications Handbook; pp. H-399-H-406
	GGAC	Gerald B. STRINGFELLOW; "Organometallic Vapor-Phase Epitaxy: Theory and Practice"; Departments of Materials Science and Engineering and Electrical Engineering, University of Utah; Academic Press, 1989
	GGAD	M.A. HERMAN, et al.; "Molecular Beam Epitaxy Fundamentals and Current Status"; Springer-Verlag Berlin Heidelberg, 1989, 1996
	GGAE	"Integration of GaAs on Si Using a Spinel Buffer Layer", IBM Technical Bulletin, Vol. 30, No. 6, Nov. 1987, p. 365.
	GGAF	"GalnAs Superconducting FET," IBM Technical Bulletin, Vol. 36, No. 8, Aug. 1993, p. 655-656.
	GGAG	"Epitaxial 3d Structure Using Mixed Spinels," IBM Technical Bulletin, Vol. 30, No. 3, Aug. 1987, p. 1271.
	GGAH	Moon et al., "Roles of Buffer Layers in Epitaxial Growth of SrTiO ₃ Films on Silicon Substrates," <i>Japan J of Appl. Phys.</i> , Vol. 33, March 1994, pp. 1472-1477.
	GGAI	Yodo et al., GaAs Heteroepitaxial Growth on Si Substrates with Thin Si Interlayers in situ Annealed at High Temperatures," 8257b Journal of Vacuum Science & Technology, 1995 May/June, Vol. 13, No. 3, pp. 1000-1005.
	GGAJ	Cuomo et al., "Substrate Effect on the Superconductivity of YBa ₂ Cu ₃ O ₇ Thin Films," AIP Conference 1988, pp. 141-148.
	GGAK	McKee et al., "Crystalline Oxides on Silicon: The First Five Monolayers," Physical Review Letters, Vol. 81, No. 14, Oct. 1998, pp. 3014-3017.
	GGAL	McKee et al., "Molecular Beam Epitaxy Growth of Epitaxial Barium Silicide, Barium Oxide, and Barium Titanate on Silicon," 1991 American Institute of Physics, pp. 782-784, August 13, 1991.
	GGAM	Tambo et al., Molecular Beam Epitaxy Growth of SrTiO₃ Films on Si(100)-2x1 with SrO Buffer Layer," <i>Jpn. J. Appl. Phys.</i> , Vol. 37, 1998, pp. 4454-4459.
	GGAN	McKee et al., "The MBE Growth and Optical Quality of BaTiO ₃ and SrTiO ₃ Thin Films on MgO," Mat. Res. Soc. Symp. Proc., Vol. 341, April 1994, pp. 309-314.
	GGAO	McKee et al., "BaSi₂ and Thin Film Alkaline Earth Silicides on Silicon," Appl. Phys. Lett., 63 (20), Nov. 1993, pp. 2818-2820.
	GGAP	McKee et al., "Surface Structures and the Orthorhombic Transformation of Thin Film BaSi₂ on Silicon," Mat. Res. Soc. Symp. Proc., Vol. 221, pp. 131-136,
	GGAQ	Brian A. FLOYD, et al.; "The projected Power Consumption of a Wireless Clock Distribution System and Comparison to Conventional Distribution Systems"; IEEE, 1999; pp. IITC99-249-IITC99-250
xaminer	l	Date Considered

*Examiner: Initial if reference is considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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BW	B		Jpn. J. of Apl. Phys., Vol. 30, No. 8A,		
	/	HHAB	Moon et al., "Growth of Crystalline Sr Properties," <i>Jpn. J. of Appl. Phys.</i> , Vo	TiO_3 Films on Si Substrates Using Thin Fluoride Bull. 33, (1994), pp. 5911-5916.	ffer Layers and Their Electrical
HHAC Farrow et al., "Heteroepitaxy of May 2, 1991.			Farrow et al., "Heteroepitaxy of Dissin May 2, 1991.	nilar Materials," Mat. Res. Soc. Symposium Procee	dings, Vol. 221, pp. 29-34, April 29
HHAD Ishiwara et al., "Heteroepitaxy o Vol. 116, pp. 369-374, April 5-8,		Vol. 116, pp. 369-374, April 5-8, 1988.		Res. Soc., Symposium Proceedings,	
		ļ		er Deposition of Thin Films; pp. 273-285	
			25-27	properties of Er³-doped BaTiO ₃ thin films"; Appl. F	
		HHAG	Kevin J. Chen et al; "A Novel Ultrafast Devices Meetingk 1996; IEEE Hong K	Functional Device: Resonant Tunneling High Electiong; June 29, 1996; pp. 60-63, XP010210167	ctron Mobility Transistor"; Electron
HHAH Wenhua Zhu et al.; "Molecular E 2; pp. 210-212			Wenhua Zhu et al.; "Molecular Beam I 2; pp. 210-212	Epitaxy of GaAs on Si-on-Insulator"; 320 Applied P	hysics Letters 59(1991) 8 July No.
HHAI Umesh K. Mishra et al; "Oxide to Digest, International; Washington		Umesh K. Mishra et al; "Oxide Based Digest, International; Washington, D.C	Compound Semiconductor Electronics"; Electron E c.; 7-10 December 1997; pp. 545-548	Devices Meeting; 1997; Technical	
		HHAJ	J.M. Daughton et al.; "Applications of s	Spin Dependent Transport Materials"; J. Phys. D. A	Appl. Phys. 32(1999) R169-R177
		HHAK	Wei Zhang et al.; "Stress Effect and E Condensed Matter; American Institute	nhanced Magnetoresistance in $La_{0.67}Ca_{0.33}MnO_{3-\delta}$ of Physics; Vol. 58, No. 21, Part 1; December 1, 1	Films"; Physical Review, B. 998; pp. 14143-14146
		HHAL	QY. Tong et al.; "IOS-a new type of n Conference, Oct. 1999; pp.104-105	naterials combination for system-on-a chip prepara	tion"; 1999 IEEE International SOI
	-	HHAM	T. Kanniainen et al.; "Growth of Dielec Electrochemical Society Proceedings,	tric 1hfo2/Ta205 Thin Film Nanolaminate Capacito U.S. Electrochemical Society; Pennington, N.J.; A	rs By Atomic Layer Epitaxy"; ugust 31, 1997; pp. 36-46
			13, 1995; pp. 1331-1333	rth of BaTio₃ Films on Si by Pulsed Laser Deposition	
		ПНАО	Myung Bok Lee; "Formation and Chara Applied Physics Letters; Vol. 34; 1995;	acterization of Eptiaxial TiO $_2$ and BaTiO $_3$ /TiO $_2$ Film; pp. 808-811	s on Si Substrate"; Japan Journal

*Examiner: Initial if reference is considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

Examiner

HHAP Gilbert Lecarpentier et al.; "High Accuracy Machine Automated Assembly for Opto Electronics"; 2000 Electronic Components and Technology Conference; pp. 1-4

Date Considered

HHAQR. Ramesh; "Ferroelectric La-Sr-Co-O/Pb-Zr-Ti-O/La-Sr-Co-O Heterostructures on Silicon via Template Growth"; 320 Applied Physics Letters; 63(1993); 27 December; No. 26; pp. 3592-3594

Form PTO 1449 U.S. DEPARTMENT OF COMMERCE 4 2003 TENT AND TRADEMARK OFFICE

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RENCES CITED BY APPLICANT

ATTY DOCKET NO.

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APPLICANT

FILING DATE

July 10, 2001

OTHER REFERENCES (Including Author, Title, Date, Pertinent Pages, etc.) K. Eisenbeiser; "Field Effect Transistors with SrTiO₃ Gate Dielectric on Si"; Applied Physics Letters; Vol. 76, No. 10; March 6, 2000; pp. 1324-1326 IIAB Stephen A. Mass; "Microwave Mixers"; Second Edition; 2pp. Douglas J. Hamilton et al.; "Basic Integrated Circuit Engineering"; pp.2; 1975 IAC Takeshi Obata; "Tunneling Magnetoresistance at Up to 270 K in La_{0.8}Sr_{0.2}MnO₃/SrTiO₃/La_{0.8}Sr_{0.2}MnO₃ Junctions with 1.6nm-Thick Barriers"; Applied Physics Letters; Vol. 74, No. 2; 11 January 1999; pp. 290-292 Wei Zhang et al.; "Enhanced Magnetoresistance in La-Ca-Mn-O Films on Si Substrates Using YbaCuO/CeO2 IIAE Heterostructures"; Physica C; Vol. 282-287, No. 2003; 1 August 1997; pp. 1231-1232 Shogo Imada et al; "Epitaxial Growth of Ferroelectric YmnO₃ Thin Films on Si (111) Substrates by Molecular Beam Epitaxy"; IIAF Jpn. J. Appl. Phys. Vol. 37 (1998); pp. 6497-6501; Part 1, No. 12A, December 1998 IAG Ladislav Pust et al.; "Temperature Dependence of the Magnetization Reversal in Co(fcc)-BN-Co(poly hcp) Structures"; Journal of Applied Physics; Vol. 85, No. 8; 15 April 1999; pp. 5765-5767 IAH C. Martinez; "Epitaxial Metallic Nanostructures on GaAs"; Surface Science; Vol. 482-485; pp. 910-915; 2001 Wen-Ching Shih et al.; "Theoretical Investigation of the SAW Properties of Ferroelectric Film Composite Structures"; IEEE IIAI Transactions of Ultrasonics, Ferroelectrics, and Frequency Control; Vol. 45, No. 2; March 1998; pp. 305-316 Zhu Dazhong et al.; "Design of ZnO/SiO2/Si Monolithic Integrated Programmable SAW Filter"; Proceedings of Fifth IIAJ International Conference on Solid-State and Integrated Circuit Technology; 21-23; October 1998; pp. 826-829 Kirk-Othmer Encyclopedia of Chemical Technology; Fourth Edition, Vol. 12; Fuel Resources to Heat Stabilizers; A Wiley-Interscience Publication; John Wiley & Sons IIAL Joseph W. Goodman et al; "Optical Interconnections For VLSI Systems"; Proceedings of the IEEE, Vol. 72, No. 7 July 1984 Fathimulla et al.; "MONOLITHIC INTEGRATION OF InGaAs/InAIAs MODFETs and RTDs on InP-bonded-to Si MAII

SUBSTRATE"; Fourth International Conference on Indium Phosphide and Related Materials, Newport, RI, USA; April 21-24

H. Takahashi et al.; "Arraryed-Waveguide Grating For Wavelength Division Multi/Demultiplexer With Nanometre

M. Schreiter, et al.; "Sputtering of Self-Polarized PZT Films for IR-Detector Arrays"; 1998 IEEE; pp. 181-185

Hideaki Adachi et al.; "Sputtering Preparation of Ferroelectric PLZT Thin Films and Their Optical Applications"; IEEE

Date Considered Examiner: Initial if reference is considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant,

Pierret, R.F.; "1/J-FET and MESFET"; Field Effect Devices; MA, Addison-Wesley; 1990; pp. 9-22

Transactions of Ultrasonics, Ferroelectrics and Frequency Control, Vol. 38, No. 6, November 1991

1992; pp. 167-170; XP000341253; IEEE, New York, NY, USA; ISBN: 0-7803-0522-1

REsolution"; Electronics Letters; Vol. 26., No. 2, 18th January 1990

NPE				SHEET 22 OF 23
Form PTO 144 (Modified)	19 4	U.S. DEPARTMENT OF COMMERCE ATENT AND TRADEMARK OFFICE	ATTY DOCKET NO.	SERIAL NO.
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		OTHER REFERENCES	(Including Author, Title, Date, Pertinent Pages,	etc.)
N.10	JJAA	A.J. Moulson et al.; "Electroceramics	Materials Properties Applications"; Chapman & Ha	all; pp. 366-369
1 13VB	İ			
	JJAB P.A. Langjahr et al.; "Epitaxial Growth and Structure of Cubic and Pseudocubic Perovskite Films on Perovskite Mat. Res. Soc. Symp. Proc., Vol. 401; 1995 Materials Research Society; pp. 109-114			
JJAC Wang et al.; "Depletion-Mode GaAs MOSFETs with Negligible Drain Current Drift and Hysteresis"; Electron D 1998, IEDM '98 Technical Digest; pp. 67-70				ysteresis"; Electron Devices Meeting
JJAD Ben G. Streetman; "Solid State Electronic Devices"; 1990, Prentice Hall; Toldan JJAE A.Y Wu et al.; "Highly Oriented (Pb,La)(Zr,Ti)O ₃ Thin Films on Amorphous			ronic Devices"; 1990, Prentice Hall; Third Edition; p	р. 320-322
			a)(Zr,Ti)O ₃ Thin Films on Amorphous Substrates";	IEEE, 1992; pp. 301-304
JJAF Timothy E. Glassman et al.; "Evidence for Cooperative Oxidation of Mot Mat. Res. Soc. Symp. Proc. Vol. 446, 1997 Materials Research Society;			e for Cooperative Oxidation of MoCVD Precursors 1997 Materials Research Society; pp. 321-326	Used in Ba _x Sr _{1-x} TiO ₃ Film Growth";
JJAG S.N. Subbarao et al.; "Monolithic PIN Photodetector and FET Amplifier of 166; 1989			Photodetector and FET Amplifier on GaAs-os-Si*;	IEEE; GaAs IC Symposium-163-
JJAH T.A. Langdo et al.; "High Quality Ge on Si by Epitaxial Necking"; Applied Physics Lett June 19, 2000			s; Vol. 76, No. 25; pp. 3700-3702;	
JJAI Chenning Hu et al.; Solar Cells From Basics to Advanced Systems; McGraw-Hill Book Company			company; 1983	
	JJAJ	O.J. Painter et al; "Room Temperature Lightwave Technology, Vol. 17, No. 1	e Photonic Crystal Defect Lasers at Near-Infrared 1; November 1999	Wavelengths in InGaAsp"; Journal of
JJAK C. Donn et al.; "A 16-Element, K-Band Monolithic Active Receive Phased Arra International Symposium, 1988; pp.188-191, Vol. 1; 6-10 June 1988 JJAL Don W. Shaw; "Epitaxial GaAs on Si: Progress and Potential Applications"; N			d Monolithic Active Receive Phased Array Antenna 38-191, Vol. 1; 6-10 June 1988	"; Antennas and Propagation Society
			Progress and Potential Applications"; Mat. Res. S	oc. Symp. Proc.; pp.15-30; 1987
	JJAM	G.J.M. Dormans, et al.; "PbTiO/ ₃ /Thin Symposium on Integrated Ferroelect	n Films Grown by Organometallic Chemical Vapou rics; April 3-5, 1991 (Abstract)	r Deposition"; Third International
	NALL	P.J. Borrelli et al.; "Compositional and Symposium; Dec. 2-4, 1991 (Abstract	d Structural Properties of Sputtered PLZT Thin Filr tt)	ns"; Ferroelectric Thin Films II
	JJAO	Ranu Nayak et al; "Enhanced acoust heterostructure"; 1 November 2000; \	o-optic diffraction efficiency in a symmetric SrRiO3 Vol. 39, No. 31; Applied Optics; pp. 5847-5853	/BaTiO3/SrTiO3 thin-film
	JJAP	Ranu Nayak et al; "Studies on acoust Phys. D: Appl. Phys. 32 (1999) 380-	to-optical interaction in SrTiO3/BaTiO3/SrTiO3 epi 387	taxial thin film heterostructures"; J.
	JJAQ	S.K. Tewksbury et al.; "Cointegration or Proceedings, Fifth Annual IEEE; 20 Ja	of Optoelectronics and Submicron CMOS"; Wafer anuary 1993; pp. 358-367	Scale Integration; 1993;

*Examiner: Initial if reference is considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

Date Considered

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	ADEM		OTHER REFERENCES (Including Author, Title, Date, Pertinent Pages, e	tc.)		
KKAA V. Kaushik et al.; "Device Characteristics of Crystalline Ep Conference Digest 58th DRC; pp. 17-20; June 19-21, 2000			V. Kaushik et al.; "Device Characteris	tics of Crystalline Epitaxial Oxides on Silicon"; Devi			
KKAB Katherine Derbyshire; "Prospects Bright for Optoelectronics Volume, Cost Drive Manufacturing for Optical A Semiconductor Magazine; Vol. 3, No. 3; March 2002 KKAC Alex Chediak et al; "Integration of GaAs/Si with Buffer Layers and Its Impact on Device Integration"; TICS 4 MSE 225, April 12, 2002; pp. 1-5				cturing for Optical Applications";			
				ntegration"; TICS 4, Prof. Sands.			
KKAD S.A. Chambers et al; "Band Discontinuities at Epitaxial SrTiO3/Si(001) Heterojunctions"; Applied Phy No. 11; September 11, 2000; pp. 1662-1664 KKAE H. Wang et al.; "GaAs/GaAlAs Power HBTs for Mobile Communications"; Microwave Symposium Dig pp. 549-552			Applied Physics Letters; Vol. 77,				
			mposium Digest; 1993 IEEE; Vol. 2.				
KKAF Y. Ota et al.; "Application of Heterojunction FET to Power Amplifier for Cellular Telephone"; Electri 1994; Vol. 30, No. 11; pp. 906-907				e"; Electronics Letters; 26th May			
KKAG Keiichi Sakuno et al; "A 3.5W HBT MMIC Power Amplifier Module for Mobile Millimeter-Wave Monolithic Circuits Symposium; pp. 63-66					ations"; IEEE 1994; Microwave and		
KKAH Mitsubishi Semiconductors Press Release (GaAs FET's) November 8, 1999 pp.1-2							
KKAI R.J. Matyi et al; "Selected Area Heteroepitaxial Growth of GaAs on Silicon for Advanced Device Structure Films; 181 (1989) December 10; No. 1; pp. 213-225 KKAJ K. Nashimoto et al; "Patterning of Nb, LaOnZr, TiO3 Waveguides for Fabricating Micro-Optics Using Wee Phase Epitaxy"; Applied Physics Letters; Vol. 75, No. 8; 23 August 1999; pp. 1054-1056 KKAK Bang-Hung Tsao et al; "Sputtered Barium Titanate and Barium Strontium Titanate Films for Capacitor A Applications of Ferroelectrics, 2000; Proceedings of the 2000 12th International Symposium on Vol. 2; pp. KKAL Man Fai Ng et al; "Heteroepitaxial growth of lanthanum aluminate films derived from mixed metal nitrate: Materials Research; Vol. 12, No. 5; pp. 1306 KKAM Yuji Matsumoto et al.; "Room-Temperature Ferromagnetism in Transparent Transition Metal-Doped Tital Science; 2 February 2001; Vol. 291; pp. 854-856 KKAN S.A. Chambers et al.; "Epitaxial Growth and Properties of Ferromagnetic Co-Doped TiO2 Anatase"; Apply Vol. 79, No. 21; November 19, 2001; pp. 3467-3469			Device Structures"; 2194 Thin Solid				
					ed metal nitrates"; Journal of		
			etal-Doped Titanium Dioxide";				
			2 Anatase"; Applied Physics Letters;				
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KKAP							
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